

METHOD FOR SUPPLYING SLURRY TO POLISHING APPARATUS

ABSTRACT OF THE DISCLOSURE

A method for feeding slurry, and a slurry feeder capable of feeding slurry to a chemical mechanical polishing apparatus, are disclosed. ~~The slurry~~ Slurry is fed from the a slurry supply tank, that stores ~~for storing the~~ slurry at a given concentration, to the chemical mechanical polishing apparatuses ~~by a~~ via slurry feed pumps. ~~The operations~~ Operations of the slurry feed pumps are suspended during the a period of time other than during the a time of feeding the slurry to the chemical mechanical polishing apparatuses. A slurry feeder for feeding a slurry to the a polishing apparatus includes a pump for feeding the slurry at a flow rate Q from a slurry supply tank to the polishing apparatus. When the a given sedimentation velocity of the ~~given~~ slurry is indicated by V , the a horizontal sectional area of the slurry supply tank is set to become smaller than Q/V .